

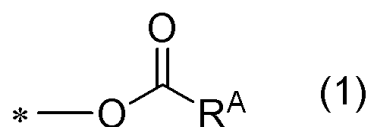
TITLE OF INVENTION: COMPOUND FOR FORMING METAL-CONTAINING FILM, COMPOSITION FOR FORMING METAL-CONTAINING FILM, AND PATTERNING PROCESS

ABSTRACT

Compound for forming a metal-containing film, represented by formula (M), where T's each represent a unit represented by formula (1); Q represents a substituted or unsubstituted alkyl group having 1 to 20 carbon atoms, a substituted or unsubstituted cycloalkyl group having 3 to 20 carbon atoms, a substituted or unsubstituted aliphatic unsaturated organic group having 2 to 20 carbon atoms and having one or more double bonds or triple bonds, a substituted or unsubstituted aryl group having 6 to 30 carbon atoms, a substituted or unsubstituted arylalkyl group having 7 to 31 carbon atoms, or a combination of these groups; and R^A represents an organic group whose protecting group is removed by an acid, heat, or both to generate one or more hydroxy groups or carboxyl groups. This provides a metal-containing film having better dry etching resistance than conventional resist underlayer film materials and having high filling and planarizing properties.



(M)



[FIG. 1]